

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Yosuke SHIRA/TA

Serial Number: 09/684,898

Filed: October 10, 2000

For: LITHOGRAPHY SYSTEM AND METHOD



Group Art Unit: 2851

Examiner: NGUYEN, H (Expected)

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PRELIMINARY AMENDMENT

Director of Patents and Trademarks  
Washington, D.C. 20231

December 21, 2000

Dear Sir:

The following amendments and remarks are respectfully submitted.

IN THE CLAIMS:

Please CANCEL claims 9, 16 and 18 without prejudice or disclaimer.

Please AMEND claims as follows:

1. (Amended) A lithography system [including] comprising:
- an exposure apparatus which [exposes] projects a pattern on to a substrate [to project a pattern onto it] on which resist is coated [, and];
- a substrate processing apparatus connected to said exposure apparatus [and adapted to process] which processes the substrate [, the system comprising:];